

1           1.    A method comprising:  
2                   forming a photoresist using a photoacid generator  
3   having a first ring including iodine or sulfur and an  
4   aromatic ring.

1           2.    The method of claim 1 including forming said  
2   first ring as a sigma-bonded ring.

1           3.    The method of claim 1 including forming an  
2   aromatic ring as a phenyl group.

1           4.    The method of claim 1 including forming a naphthyl  
2   ring structure.

1           5.    The method of claim 1 including bonding said  
2   first ring directly to said aromatic ring to form a naphthyl  
3   ring.

1           6.    A photoresist comprising:  
2                   a photoacid generator including a first ring with  
3   iodine or sulfur, and an aromatic ring bonded to said first  
4   ring.

1           7.    The photoresist of claim 6 including two aromatic  
2   rings coupled to said first ring.

1           8.    The photoresist of claim 6 wherein said first  
2 ring is sigma-bonded.

1           9.    The photoresist of claim 6 wherein said aromatic  
2 ring is a phenyl group.

1           10.   The photoresist of claim 6 wherein said first  
2 ring is directly bonded to said aromatic ring to form a  
3 naphthyl ring structure.

1           11.   A photoresist comprising:  
2                a photoacid generator including a first ring and  
3 an aromatic ring directly bonded to said first ring; and  
4                said first ring including two atoms selected from  
5 the group including iodine and sulfur.

1           12.   The photoresist of claim 11 wherein said first  
2 ring is sigma-bonded.

1           13.   The photoresist of claim 11 including two  
2 aromatic rings bonded to said first ring.

1           14.   The photoresist of claim 13 wherein said aromatic  
2 rings are bonded on opposite sides of said first ring.

1           15. The photoresist of claim 6 wherein said aromatic  
2 ring is a phenyl group.

1           16. The photoresist of claim 11 wherein said aromatic  
2 ring has an alkyl, phenyl, or caged alkyl attached to said  
3 ring.

1           17. The photoresist of claim 11 including an anion  
2 selected from the group of  $\text{ClO}_4$ ,  $\text{SbF}_6$ , and perfluoroalkyl  
3 sulfonate.